

# **Special Topics on Basic EECS I**

# **Design Technology Co-Optimization**

## **Lecture 17**

Sung-Min Hong ([smhong@gist.ac.kr](mailto:smhong@gist.ac.kr))

Semiconductor Device Simulation Laboratory

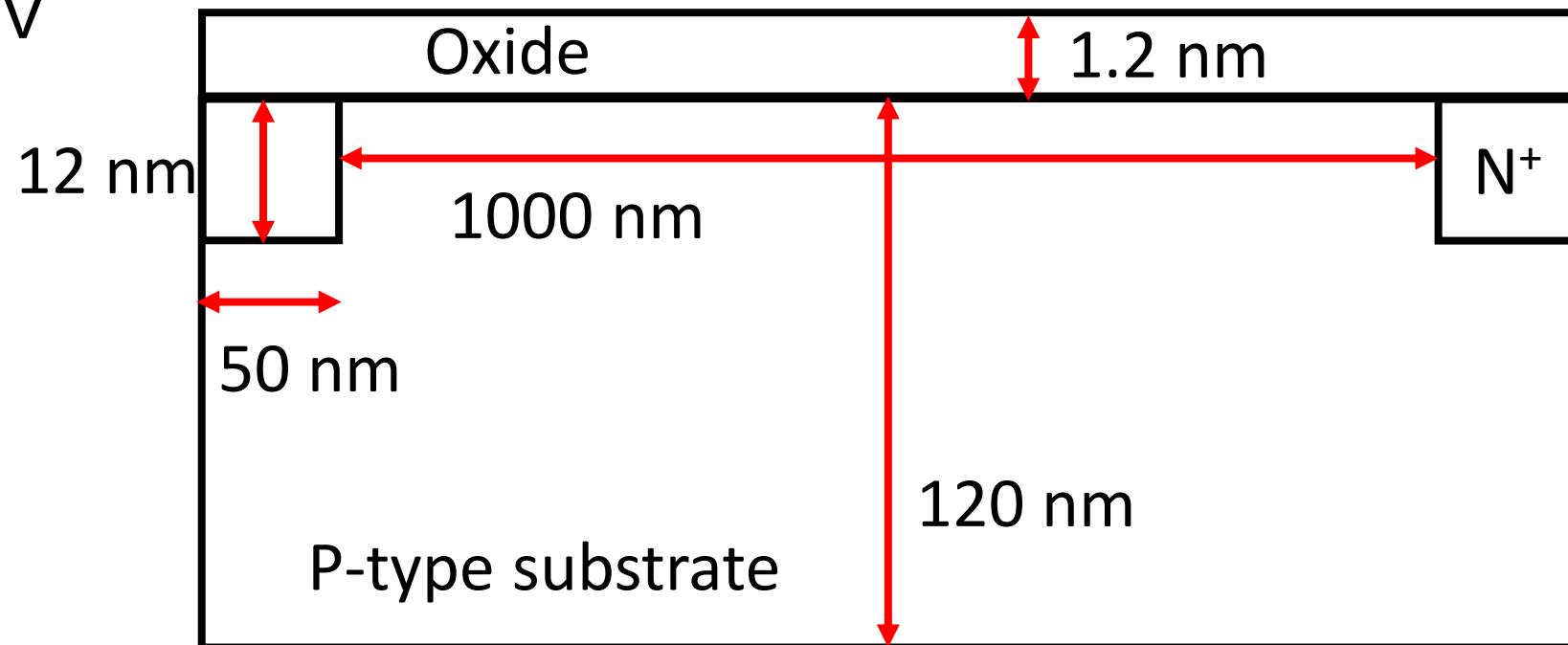
Department of Electrical Engineering and Computer Science

Gwangju Institute of Science and Technology (GIST)

# L17

# Simulation of a long-channel MOSFET

- Effective oxide thickness of 1.2 nm
  - Gate workfunction of 4.3 eV
  - Substrate doping of  $1.5 \times 10^{18} \text{ cm}^{-3}$
  - $V_{DD}$  of 1.2 V



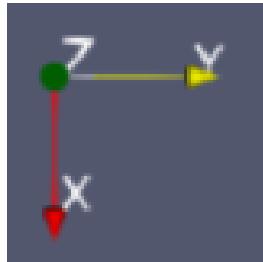
# Structure generation

- Spacing along the vertical direction: 1.2 nm
  - Spacing along the lateral direction: 5 nm
  - How many points?  $102 \times 221 = 22542$
  - Too many points for such a simple structure...
- Source/drain doping profile
  - Gaussian profile is usually used.
  - In this example, abrupt junctions are assumed.

# Mapmaker

- Input file

- $x$ : Depth
- $y$ : Channel
- $z$ : Width



```
thing (type="mapmaker",name="structure") {
    mapmaker (type="3d",cgns="long.cgns") {
        cuboid (x0=-1.2nm,y0=-550nm,x1=120nm,y1=550nm,z0=0.0,z1=1.0um,nx=102,ny=221,nz=2)
        region (name="semiconductor",material="silicon",ix0=1,ix1=101,iy0=0,iy1=220,iz0=0,iz1=1)
        region (name="insulator", material="oxide", ix0=0,ix1=1, iy0=0,iy1=220,iz0=0,iz1=1)
        doping (region="semiconductor",ix0=1,ix1=101,iy0=0, iy1=220,iz0=0,iz1=1,density=-1.5e18/cm3)
        doping (region="semiconductor",ix0=1,ix1=11, iy0=0, iy1=10, iz0=0,iz1=1,density=2e20/cm3)
        doping (region="semiconductor",ix0=1,ix1=11, iy0=210,iy1=220,iz0=0,iz1=1,density=2e20/cm3)
        contact (name="source",ix0=1, ix1=6, iy0=0, iy1=0, iz0=0,iz1=1)
        contact (name="gate", ix0=0, ix1=0, iy0=10, iy1=210,iz0=0,iz1=1)
        contact (name="drain", ix0=1, ix1=6, iy0=220,iy1=220,iz0=0,iz1=1)
        contact (name="body", ix0=101,ix1=101,iy0=0, iy1=220,iz0=0,iz1=1)
    }
}
```

# Long-channel device structure

- It is not very realistic.
  - Abrupt source/drain doping
  - Constant substrate doping
  - Spacer
  - Source/drain contact



# Loading the structure

- In a MOSFET, we have a gate contact.
  - The workfunction must be specified.
  - Do not forget to specify the bandgap narrowing model.

```
thing (type="device",name="mosfet") {
    device (type="3d",areafactor=1.0) {
        load (cgns="long.cgns",dbpath="/")
        electrode (name="gate",workfunction=4.3)
    }
}

property (thing="mosfet",model="effectiveintrinsicscdensity",nobandgapnarrowing)
```

Here goes your dbpath.

# Building a circuit

- We need (at least) two voltage sources.
  - Prepare them ( $v_g$  and  $v_d$  in this example) and build a circuit.

```
thing (type="lumped",name="vg") {
    lumped (type="v",value=0.0)
}

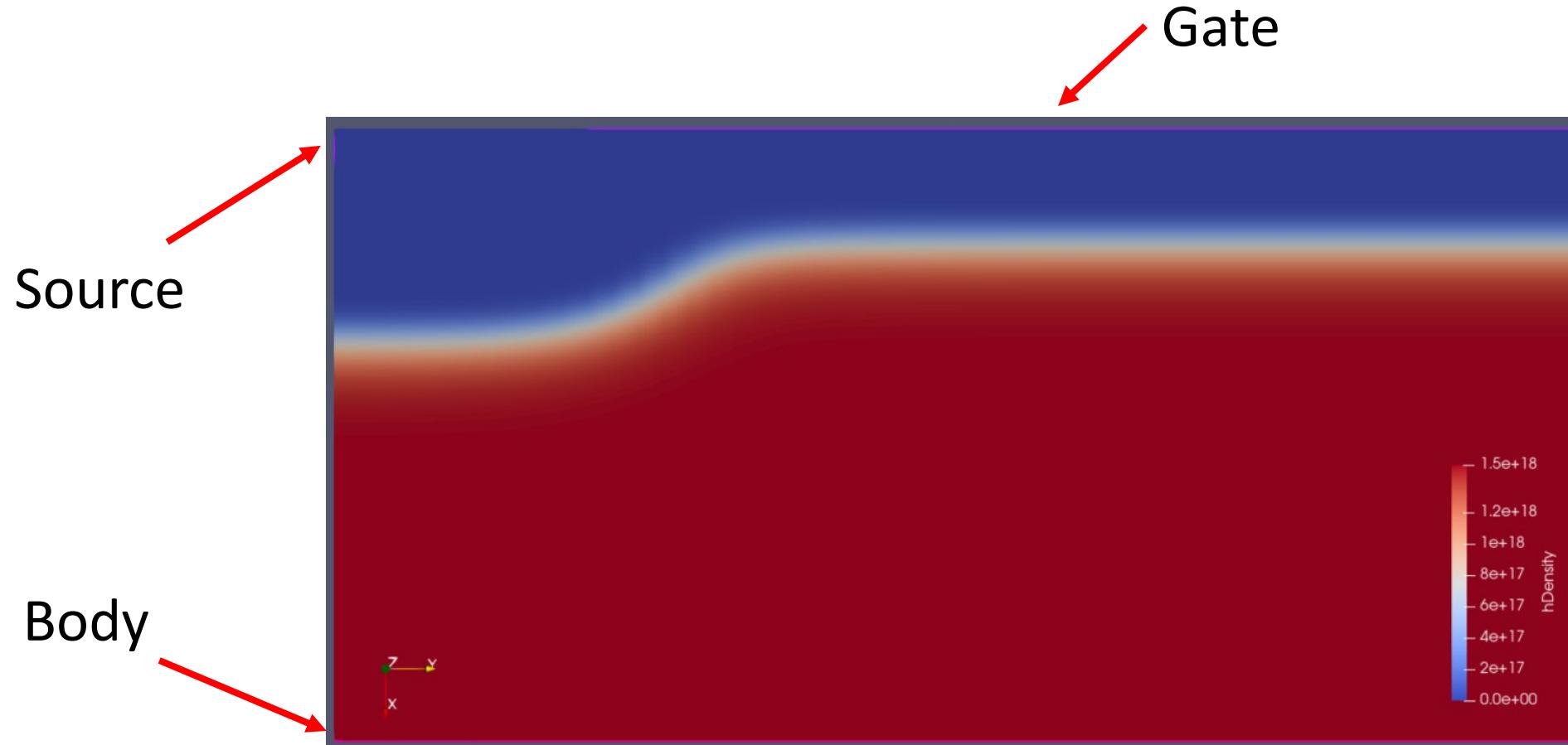
thing (type="lumped",name="vd") {
    lumped (type="v",value=0.0)
}

thing (type="circuit",name="circuit") {
    circuit {
        node (thing="gnd",name="GND")
        node (thing="mosfet", contact="source",name="GND")
        node (thing="mosfet", contact="gate" ,name="IN")
        node (thing="mosfet", contact="drain" ,name="OUT")
        node (thing="mosfet", contact="body" ,name="GND")
        node (thing="vg", contact="0" , name="GND")
        node (thing="vg", contact="1" , name="IN")
        node (thing="vd", contact="0" , name="GND")
        node (thing="vd", contact="1" , name="OUT")
    }
}
```

# Equilibrium

```
law (name="eqlaw") {  
    equation (type="poisson",thing="mosfet")  
}  
  
solve (law="eqlaw",initialstep=1.0,plot,plotprefix="long_eq",cgns)
```

- Depletion of holes



# Setting a law and a book

- Drift-diffusion simulation and IV curves
  - There are two voltage sources. Therefore, we need to specify the “virlc” equation twice.

```
law (name="dclaw",iteration=12) {  
    equation (type="poisson" ,thing="mosfet")  
    equation (type="econtinuity",thing="mosfet")  
    equation (type="hcontinuity",thing="mosfet")  
    equation (type="contact" ,thing="mosfet")  
    equation (type="virlc" ,thing="vg")  
    equation (type="virlc" ,thing="vd")  
    equation (type="kirchhoff" ,thing="circuit")  
}  
  
book (name="input_iv", csv="input_iv.csv") {  
    event (thing="mosfet", contact="gate")  
    event (thing="mosfet", contact="drain")  
}
```

# Bias ramping

- Usually, we consider two drain voltages.
  - A voltage close to zero,  $V_D \approx 0$  V & a voltage equal to  $V_{DD}$
  - In the following example, we take 0.05 V.

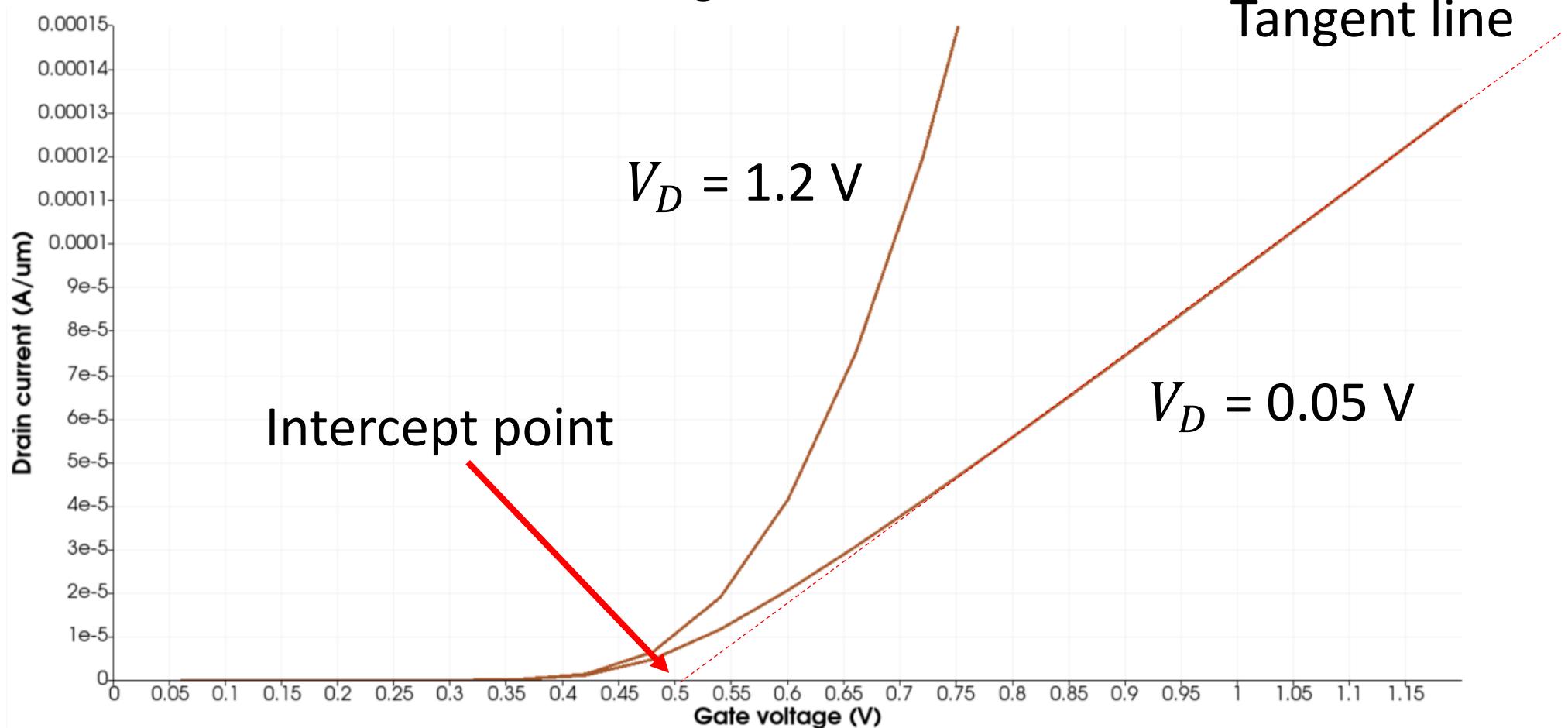
```
solve (law="dclaw",initialstep=1.0) {
    goal (thing="vd", quantity="voltage", value=0.05)
}
```

- After running this solve statement, we have a solution at  $V_G = 0$  V and  $V_D = 0.05$  V.
- Then,

```
solve (law="dclaw",initialstep=0.01,maxstep=0.01,minstep=0.01,plot,plotprefix="long_dc",cgns,book="input_iv") {
    goal (thing="vg", quantity="voltage", value=1.2)
}
```

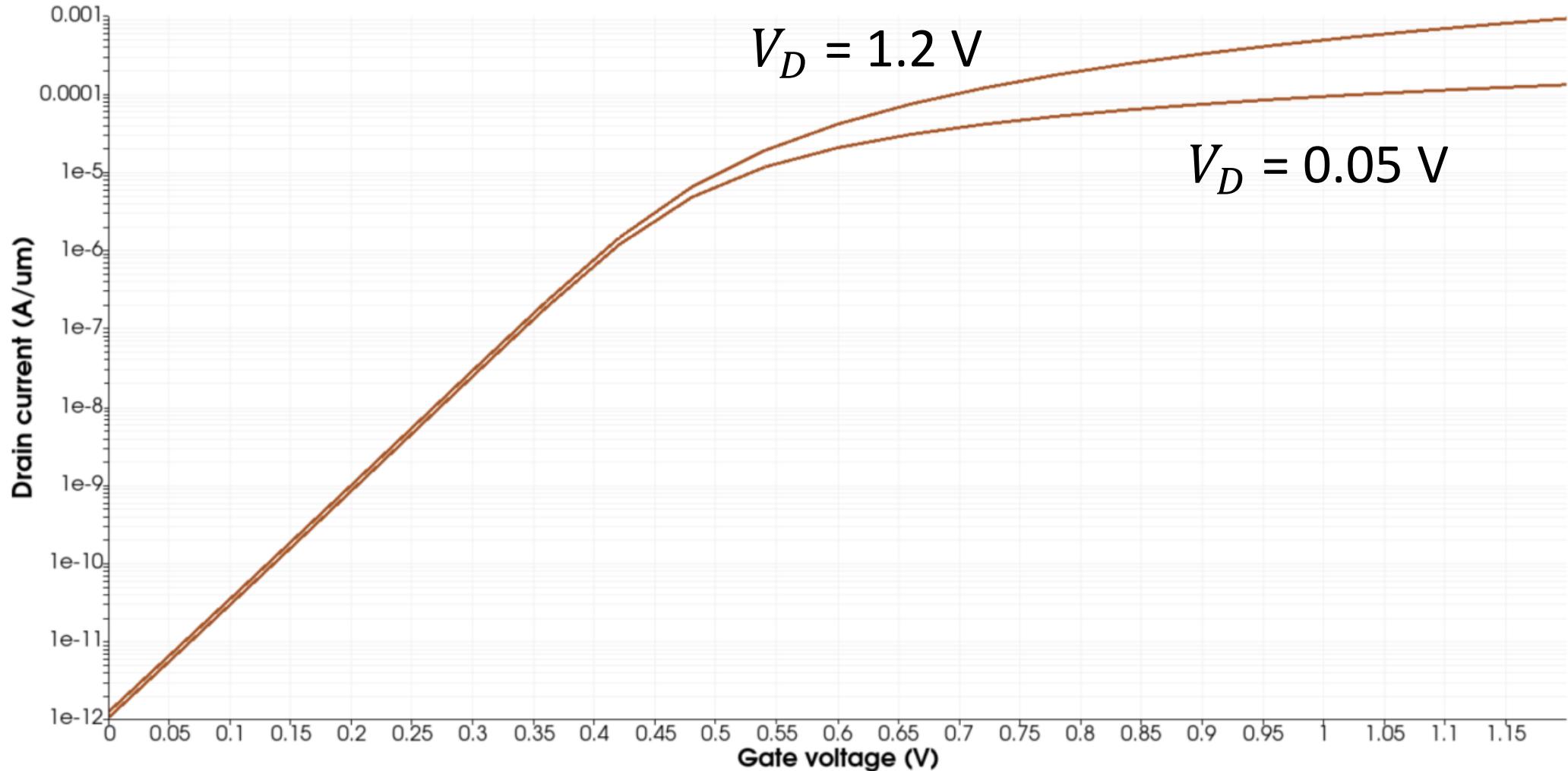
# Ramping the gate voltage up

- Results WITHOUT any physical model, from 0 V to 1.2 V
  - Estimate the threshold voltage.



# Semi-logarithmic graph

- Estimate the subthreshold slope, the DIBL,  $I_{ON}$ , and  $I_{OFF}$ .



# Physical models

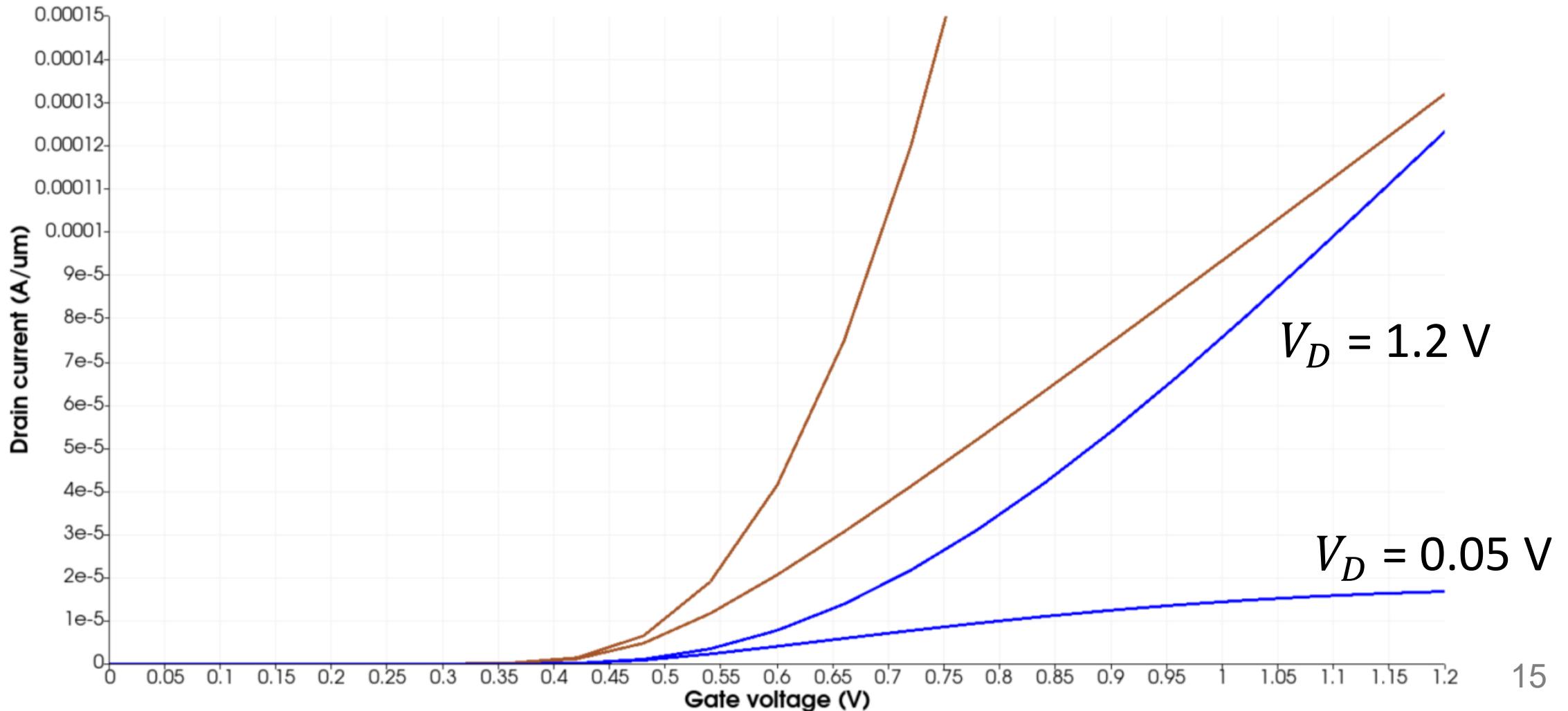
- Of course, we must include physical models.
  - Add the following lines.

```
property (thing="mosfet",model="mobility",mujtaba,canali)  
property (thing="mosfet",model="recombination",srh)
```

- Observe their effects.

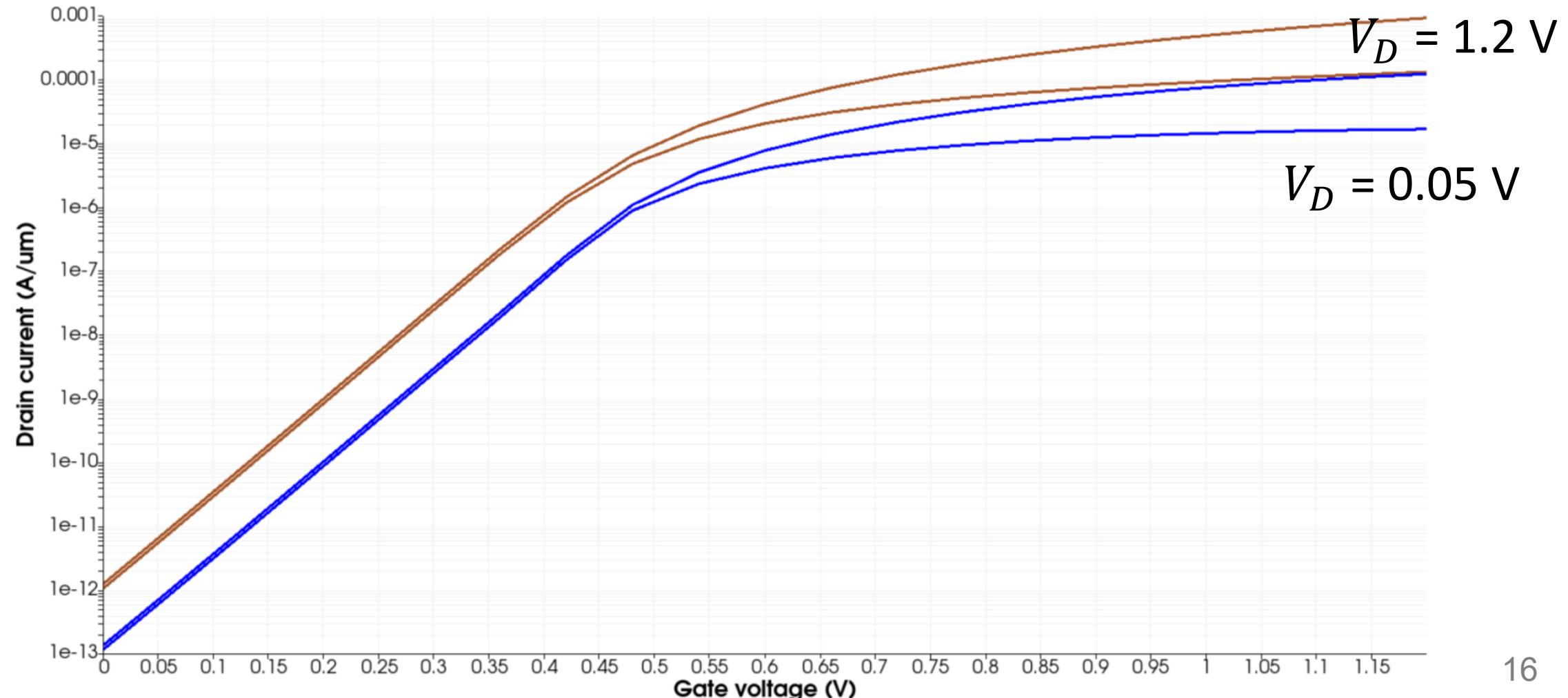
# Linear curve

- Significantly reduced current (Blue curves)



# Semi-logarithmic curve

- Significantly reduced current (Blue curves)



# Ramping the drain voltage up

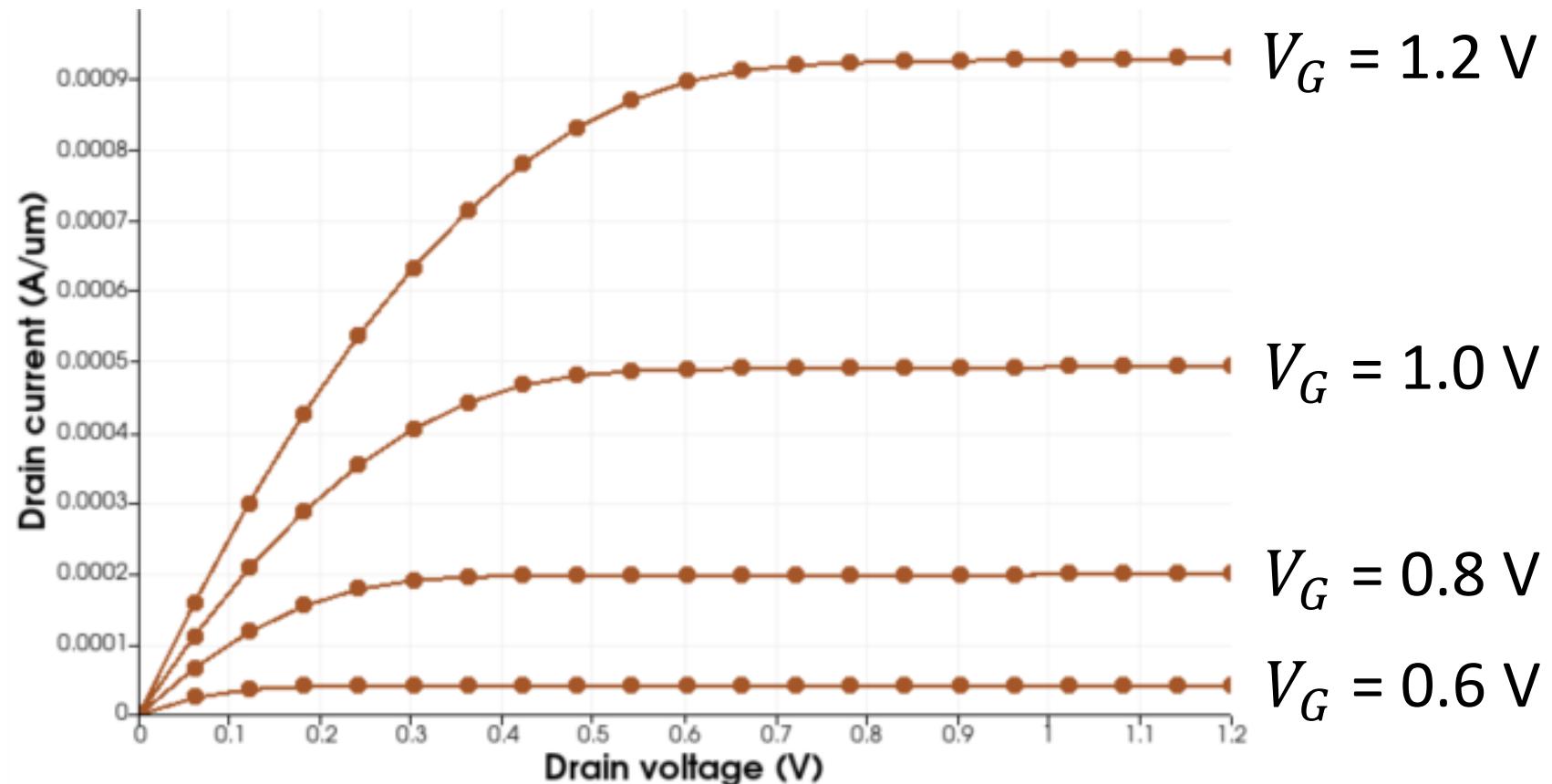
- We need several gate voltages.
  - Select a value and ramp up the gate voltage.
- Increase the drain voltage from 0 V to  $V_{DD}$ .

```
solve (law="dclaw",initialstep=0.05,maxstep=0.05,minstep=0.01,dozero,  
      plot,plotprefix="long_dc",cgns,book="output_iv") {  
    goal (thing="vd", quantity="voltage", value=1.2)  
}
```

- Repeat it with other  $V_G$  values.

# Without physical models

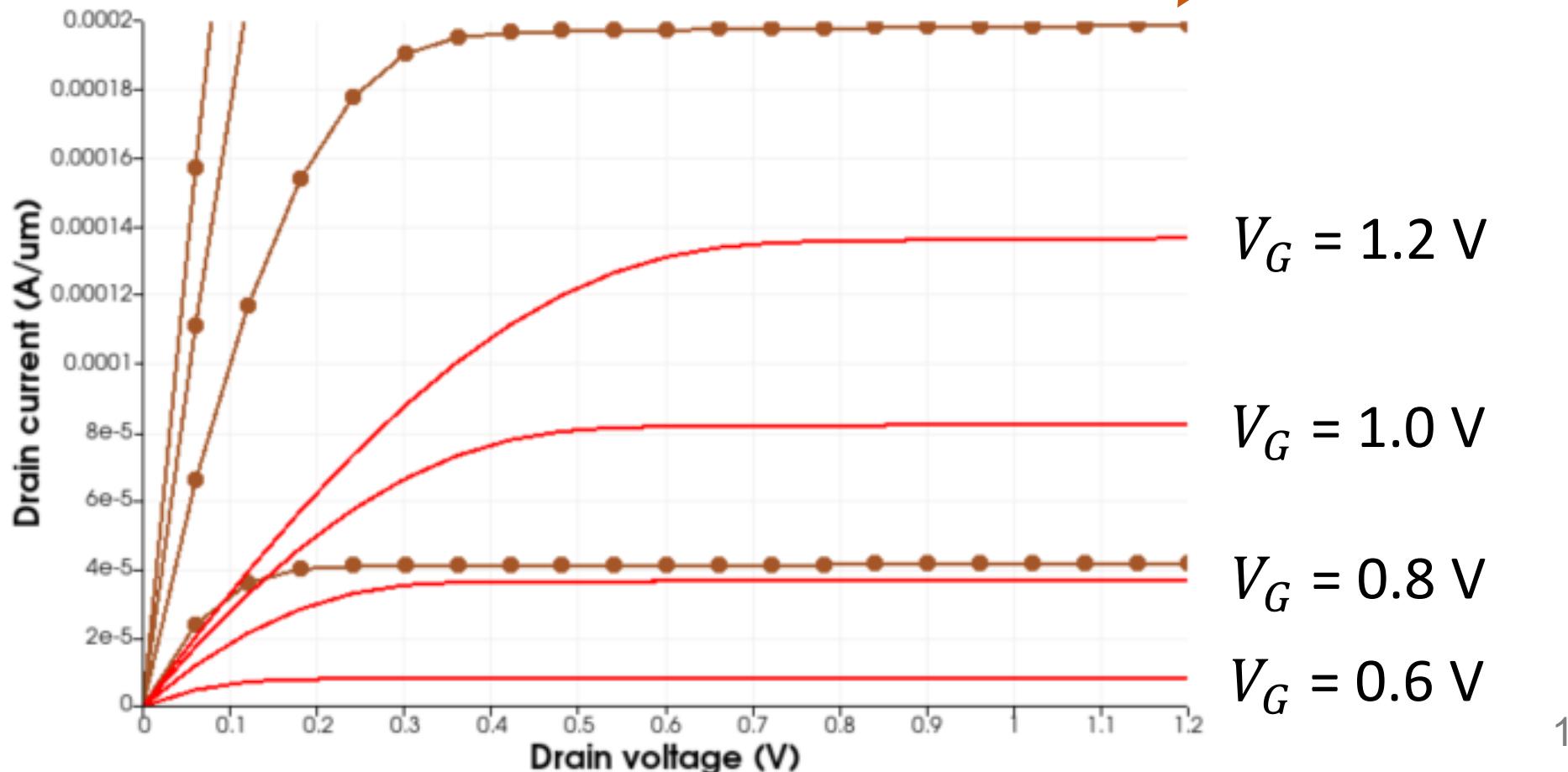
- Results WITHOUT any physical model from  $V_G = 0.6 \text{ V}$  to  $1.2 \text{ V}$  ( $0.2 \text{ V}$  step)



# Inversion mobility model

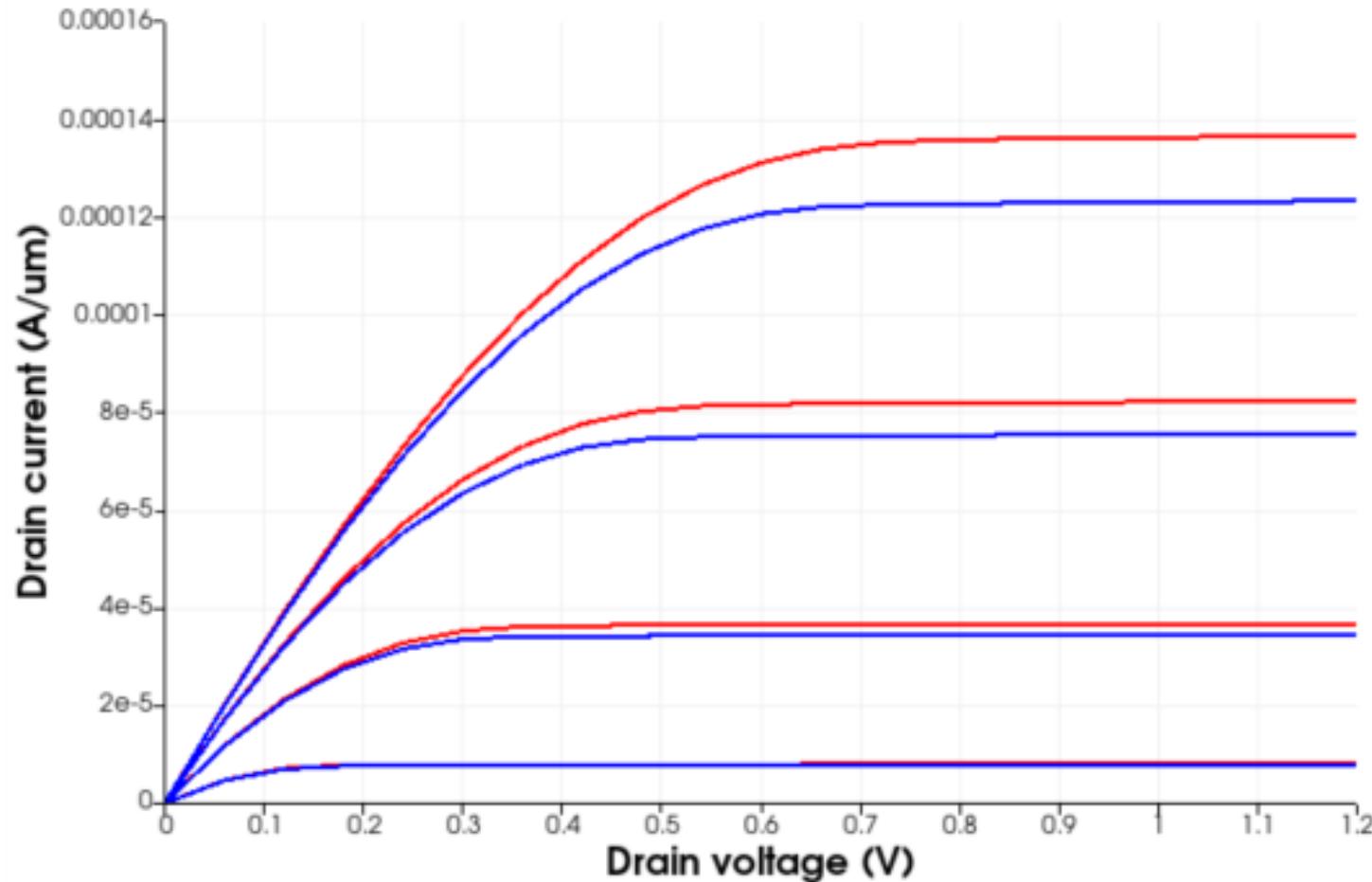
- Results WITH inversion mobility model

- Significantly reduced current (Brown versus red)



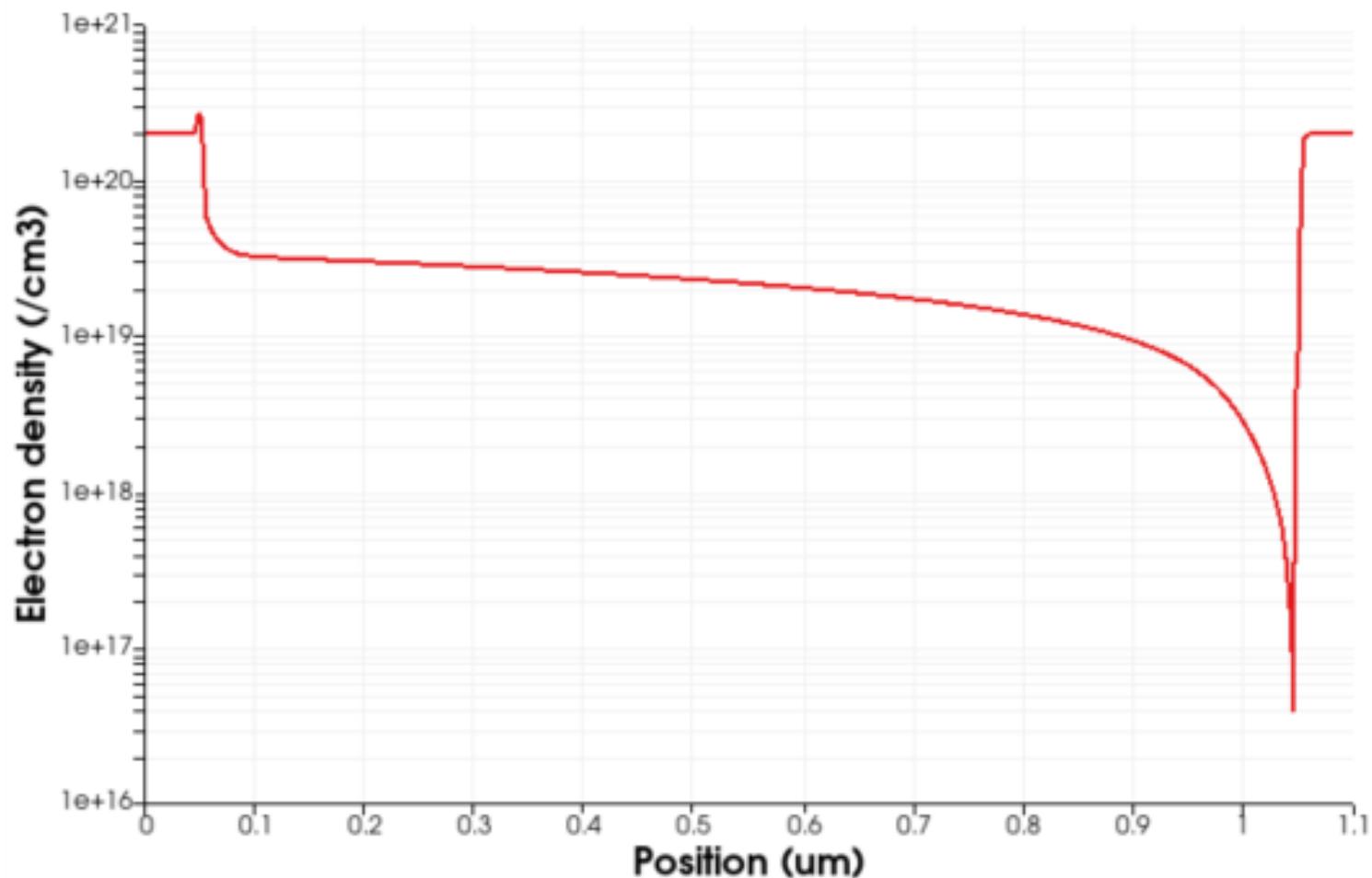
# Velocity saturation

- Results WITH inversion mobility model + velocity saturation



# Electron density

- Interface carrier density at  $V_G = V_D = V_{DD}$



# Homework#17

- Due: 08:00 on Nov. 17
- Submit a report through the GIST LMS system.
  - From the input IV characteristics of our long-channel MOSFET, estimate the DIBL. (Of course, you must consider physical models.)

# Thank you!